Supporting information

For

Formation of submicron-sized silica patterns on flexible polymer substrates based on vacuum ultraviolet photo-oxidation

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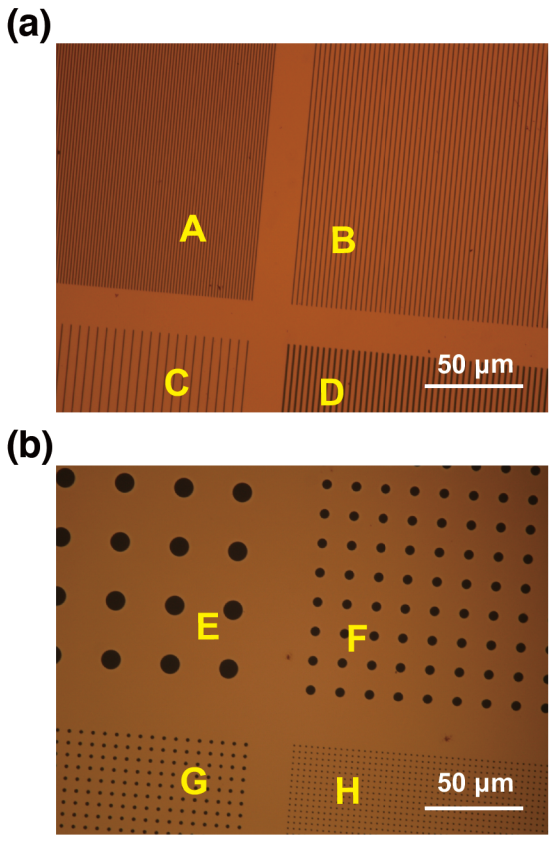

Figure S1. Optical micrographs of photomasks with (a) line patterns and (b) circular patterns. (a) Domain A, B, C, D represent the regions, which have (interval, line width) of (1 μm, 0.5 μm), (2 μm, 0.5 μm), (4 μm, 0.5 μm), and (2 μm, 1 μm), respectively. (b) Domain E, F, G, H represent the regions, which have circular patterns with diameters of 10 μm, 5 μm, 2 μm, 1 μm, respectively.

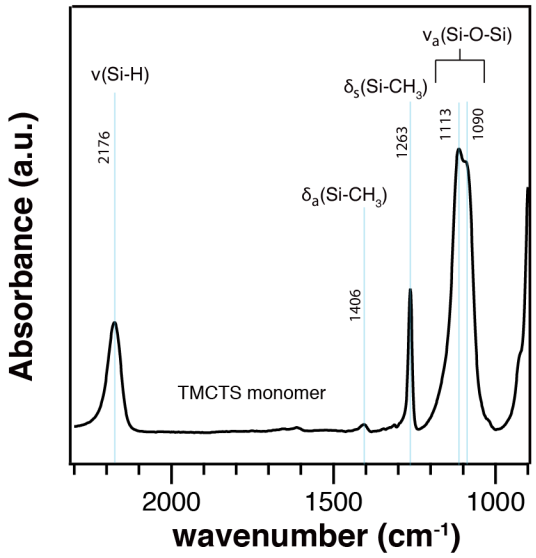

Figure S2. IR spectra of TMCTS monomer.